



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. .... 09/536,037  
Confirmation No. .... 4099  
Filing Date ..... March 27, 2000  
Inventor ..... Li et al.  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2822  
Examiner ..... Toniae M. Thomas  
Attorney's Docket No. .... MI22-1398  
Customer No. .... 021567  
Title: Low k Interlevel Dielectric Layer Fabrication Methods

**PRELIMINARY AMENDMENT TO ACCOMPANY RCE FILING**

To: Mail Stop RCE  
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**REMARKS**

This Request for Continued Examination is submitted in an abundance of caution simply to place certain references before the Examiner for consideration. The references are referred to in the Information Disclosure Statement presented herewith.

No new matter is being presented in this application.